

Emoj
Docket: CS 99 - 065CC
S/N: 09/442,499



1703

To: Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

From: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject:

Serial No.: 09/442,499	Filed: 11/18/1999
Inventor: Ho	
Title: Plasma Etch Method For Forming Plasma Etched Silicon Layer	
Group Art Unit: 1763	Examiner: Goudreau, G. A.
Attorney Docket: CS 99 - 065CC	

RESPONSE TO PATENT OFFICE ACTION

Dear Sir:

In response to the office action dated 10/23/2003 and to the Notice of Non-Compliant Amendment mailed February 23, 2004 please consider the following remarks:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450, on March 23, 2004.

Signature/Date

3/23/04

Stephen B. Ackerman
Reg. No. 37,761

Charge to Deposit Account

The Commissioner is hereby authorized to charge payment of the fee of \$_____ associated with this communication, or credit any overpayment, to Deposit Account No. 19-0033. The Commissioner is also authorized to charge any additional fee under 37 CFR §1.16 and 1.17 to this Deposit Account. A duplicate copy of this sheet is enclosed. The Commissioner is hereby authorized to charge payment of any additional fees involved with added Claims and the like to Deposit Account No. 19-0033.

Respectively submitted,

Date

George O. Saile; or

Stephen B. Ackerman